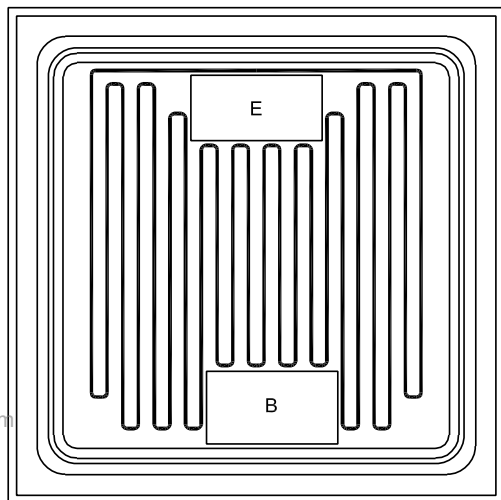


PROCESS CP283
Power Transistor
NPN - Silicon Power Transistor Chip

PROCESS DETAILS

Die Size	68 x 68 MILS
Die Thickness	9.5 MILS
Base Bonding Pad Area	18 x 11 MILS
Emitter Bonding Pad Area	18 x 12 MILS
Top Side Metalization	Al - 45,000Å
Back Side Metalization	Ti/Ni/Ag - (3000Å, 10,000Å, 10,000Å)

GEOMETRY



GROSS DIE PER 5 INCH WAFER

3,675

PRINCIPAL DEVICE TYPES

MJE13003

www.DataSheet4U.com

BACKSIDE COLLECTOR

R0

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R0 (20-January 2006)